

What is claimed is:

1. An apparatus for removing particles for a processing device including a vacuum container unit having a plurality of chambers in which a predetermined process is performed on a wafer carried in by a conveyer unit which is
5 under atmospheric pressure, the apparatus comprising:

a charge neutralizing means for neutralizing charges generated on a surface of the wafer, the charge neutralizing means being mounted in a waiting-accommodation
10 unit which constitutes a part of the conveyer unit; and

a charging means for adsorbing particles in the vacuum container unit by electrostatic force, the charging means being mounted in the vacuum container unit.

15 2. An apparatus according to claim 1, wherein the charge neutralizing means performs neutralization of the charges generated on the surface of the wafer by a discharge from an electrode mounted at a predetermined distance apart from the wafer.

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3. An apparatus according to claim 1, wherein the charging means comprises a metal plate mounted apart from the wafer moving in the vacuum container unit and adsorbs the particles by charging the metal plate.

4. An apparatus according to claim 3, wherein the metal plate comprises internal plate electrodes mounted along the inner side of chamber side walls and external plate electrodes mounted along the outer side of chamber side walls to be opposed to the internal plate electrodes.

5. A method of removing particles for a processing device including a vacuum container unit having plurality of chambers in which a predetermined process is performed on a wafer carried in by a conveyer unit in atmosphere, the method comprising the steps of:

neutralizing charges generated on the surface of the wafer in a waiting-accommodation unit which constitutes a part of the conveyer unit; and

adsorbing particles existing in the vacuum container unit by electrostatic force.